

# SiN films: Characterization workflow and examples from analysis

*work-in-progress report*

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# The scientific case

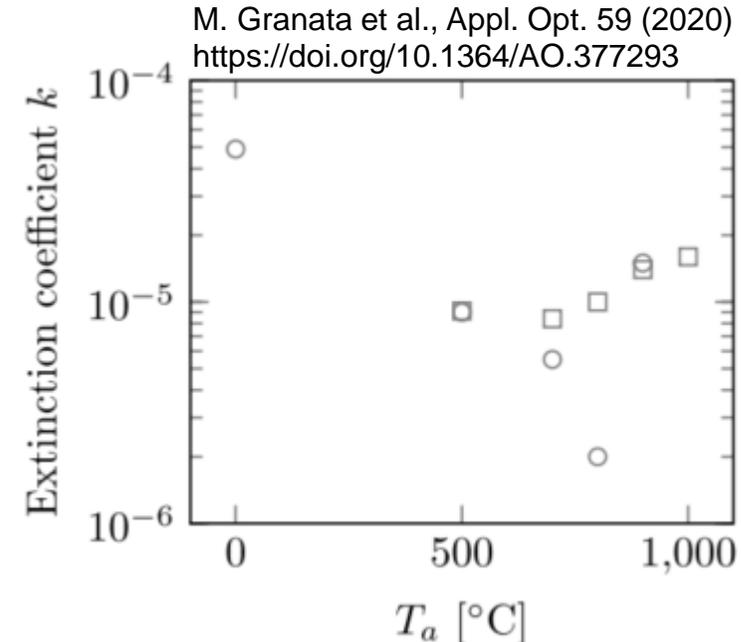
- Silicon Nitride coatings

- Losses are about 3 times lower than present Ta<sub>2</sub>O<sub>5</sub>-TiO<sub>2</sub> coatings
- Can be annealed up to 900 °C without crystallization
- Optical absorption is relatively high and has to be reduced

Challenge:  
*increase n, decrease k*

**Table 2. Tentative Projection of Requirements for Optical and Mechanical Properties of Coating Layers for Future GW Interferometers, Based on Current Standards (from Refs. [4,30] and This Work)**

Refractive Index	$n_H > 2.09$ $n_L < 1.45$
Extinction	$10^{-7} < k < 10^{-6}$
Scattering	$\alpha_s \leq 10$ ppm
Internal friction	$\phi_c < 10^{-4}$ at 100 Hz
Coated diameter	$d \geq 35$ cm
Thickness uniformity	$\Delta t_c \leq 0.1\%$
Surface roughness	$\leq 0.1$ nm rms



- Factors affecting the optical absorption & refractive index

- Stoichiometry (S/N ratio)
- Oxygen
- Hydrogen
- Contaminants
- Coating (in)homogeneity
- Density

Literature studies help  
(only up to a certain point...)

Example: silicon-rich SiNx films have higher absorption [Paule et al., Vacuum 37:395, 1987]

- Characterization is required to track ALL the above factors, so that they can be optimized during the next fabrication campaign

# Tracking the factors affecting absorption



## Optical properties

Quantity	Technique	Group
n	Spectrophotom. Ellipsometry	LMA Genova
k	Spectrophotom. Phototherm. defl. Ellipsometry	LMA " Genova
gradient	Spectrophotom. Ellipsometry	LMA Genova

## Chemical/compositional properties

Quantity	Technique	Group
Stoichiometry, H content, O content, Contaminants	EDX XPS " Raman LIBS FTIR RBS SIMS ERDA RBS	Perugia Roma1 Genova g-MAG g-MAG Padova " " SAFIR/ Navier

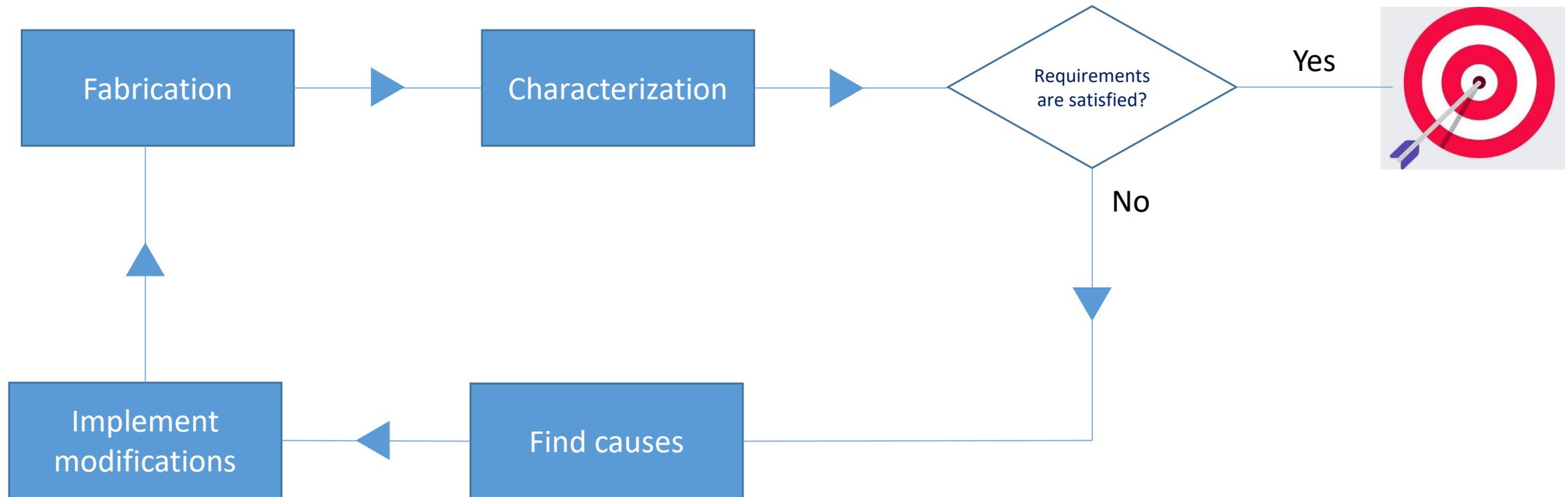
## Morphological/structural properties

Quantity	Technique	Group
Thickness	Spectroph. Ellipsom.	LMA Genova
Surface analysis	SEM AFM	Perugia "
Density, roughness	XRR	Padova
Cryst. content	GIXRD	"

The results from the characterization are evaluated and discussed by considering the theory describing the amorphous coatings (Navier)

*NOTE: concerning the thermo-optic effect in SiNx coatings, see the poster by **Matteo Bisch** on 20 May*

# Workflow

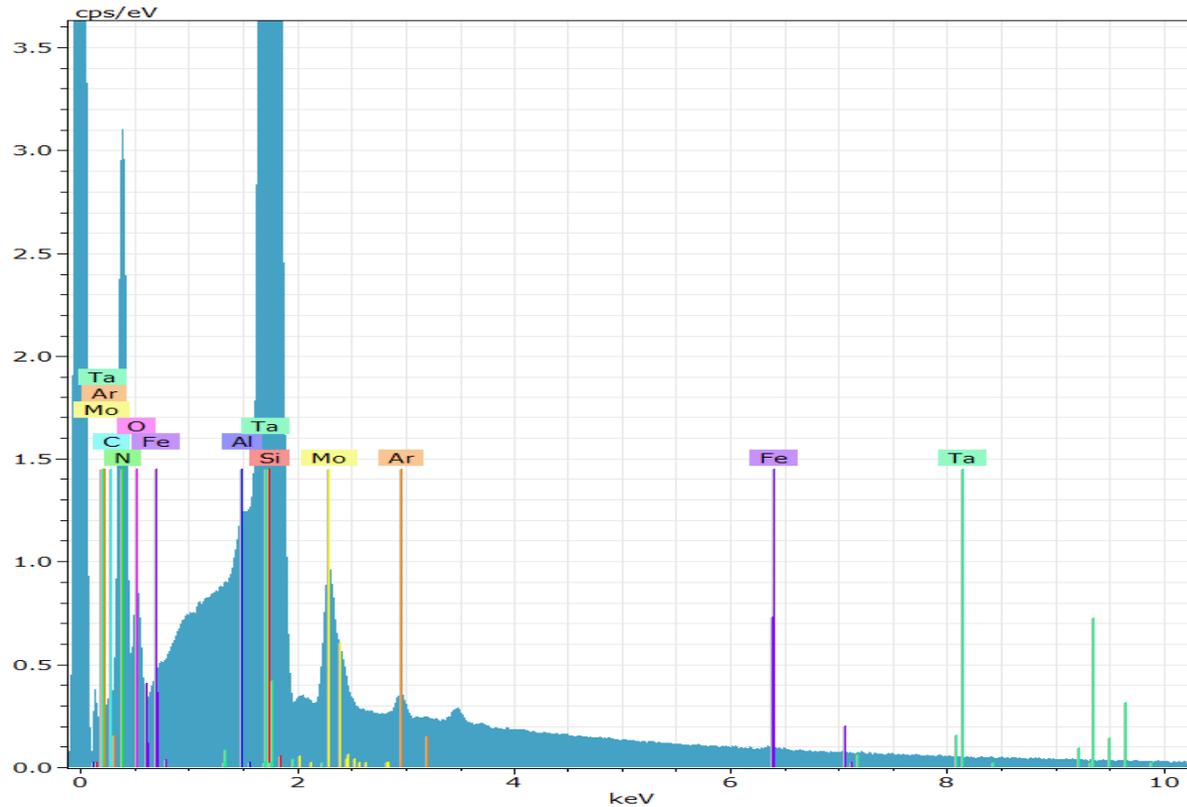


So far: **4 batches of SiN films** have been produced by LMA and distributed to VCR&D for characterization. Other samples will be available soon.

# Example of analysis (sample prod. date: dec2020-jan2021)



## EDX data and analysis (Perugia)

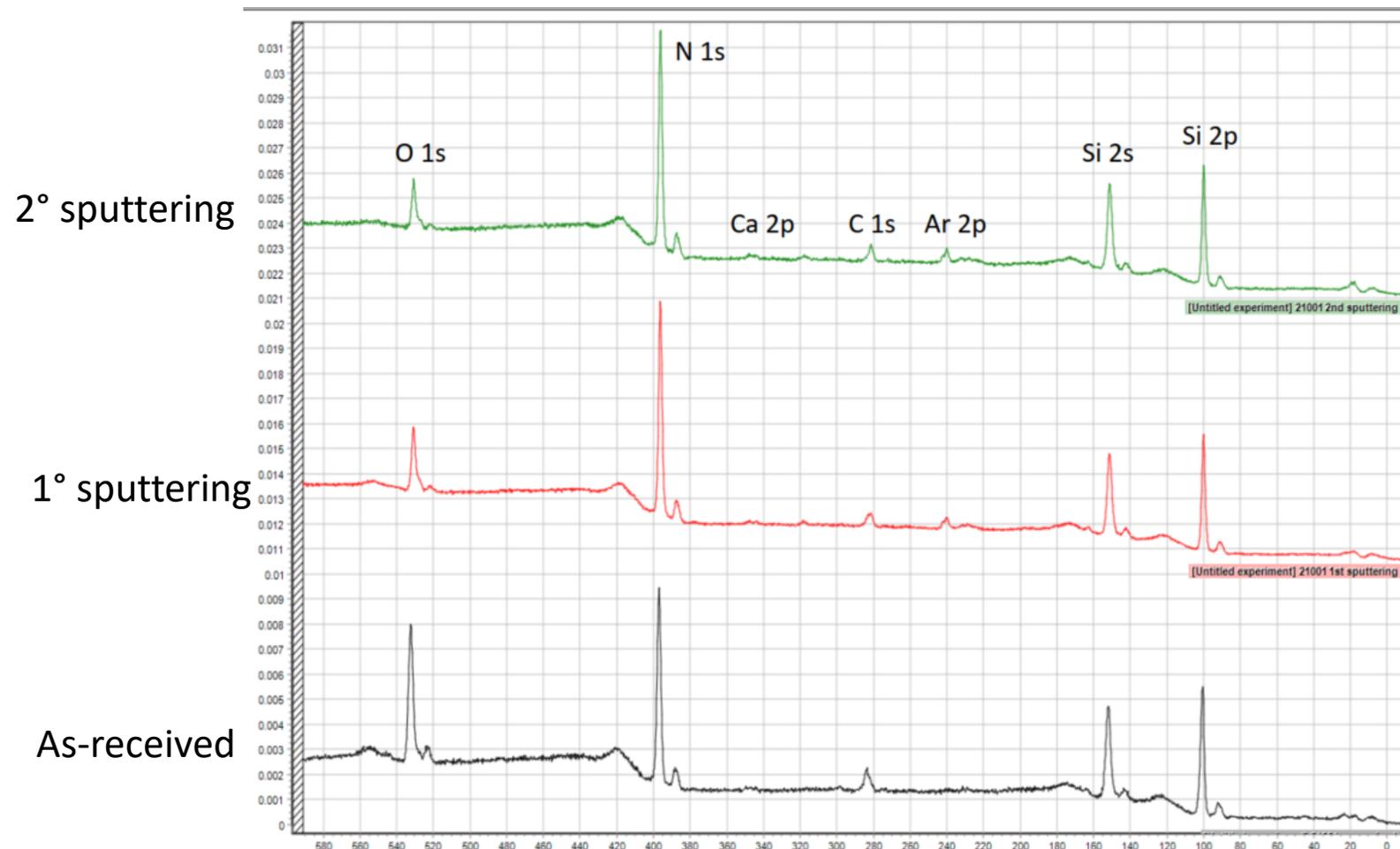


Element	series	[norm. wt.%]	[norm. at.%]	Error in wt.% (1 Sigma)
Silicon	K-series	62.43918541	48.89649742	2.608289506
Nitrogen	K-series	27.58287787	43.31181983	3.094118152
Aluminium	K-series	0.425638601	0.346958026	0.044989492
Carbon	K-series	0	0	0
Oxygen	K-series	4.548775018	6.253072217	0.581343653
Molybdenum	L-series	3.105090425	0.711831517	0.134403896
Argon	K-series	0.359018787	0.197662736	0.037264495
Tantalum	L-series	LOD	LOD	LOD
Iron	K-series	0.349075697	0.137474594	0.037868634
Sum:		100	100	

Si/N ratio: 1.129

# Example of analysis (sample prod. date: dec2020-jan2021)

## XPS data before and after sputtering (Roma1)

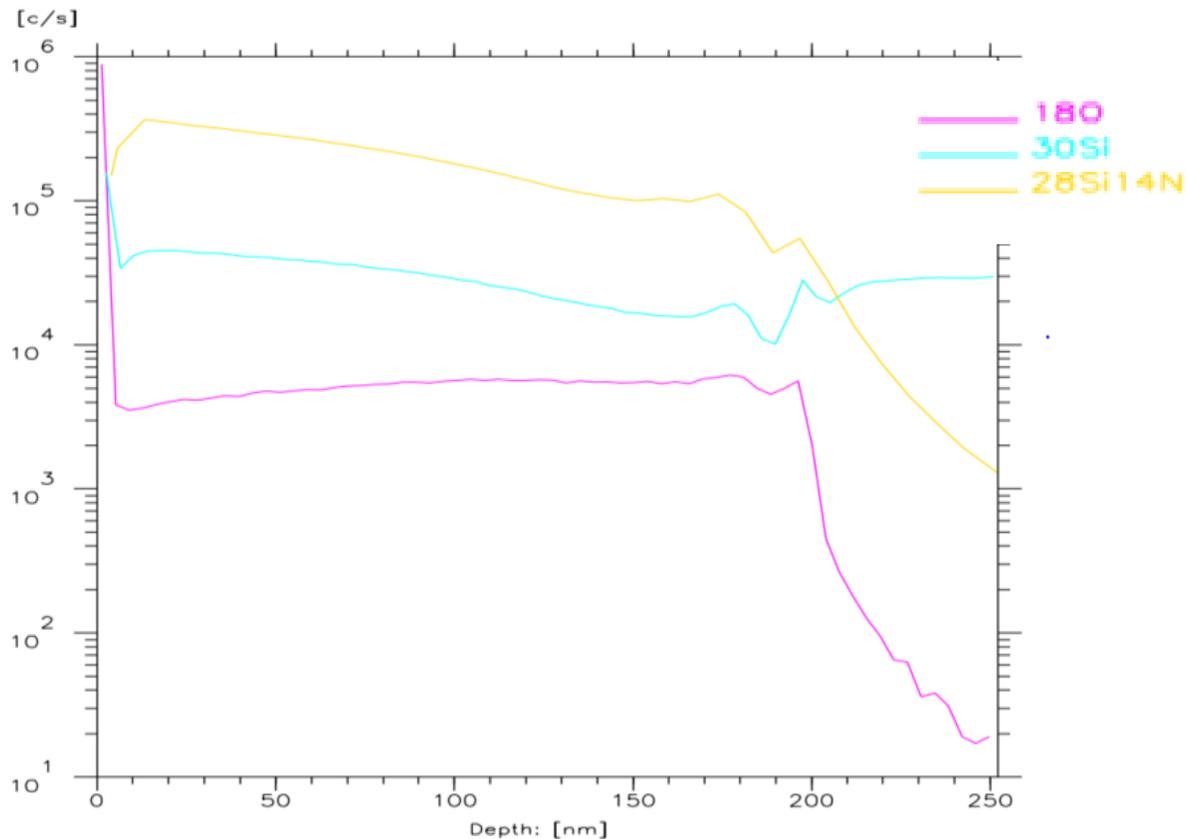


Note:  
O content decreases  
as depth is increased

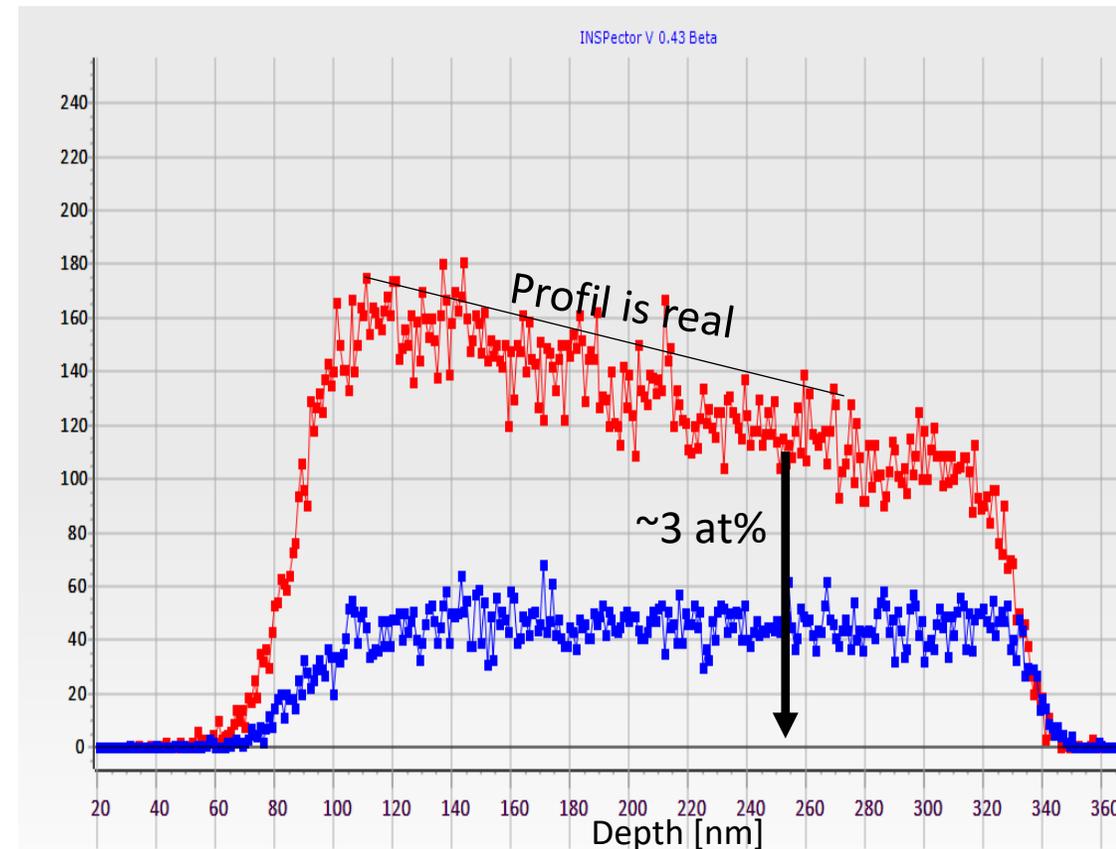
# Example of analysis (sample prod. date: dec2020-jan2021)



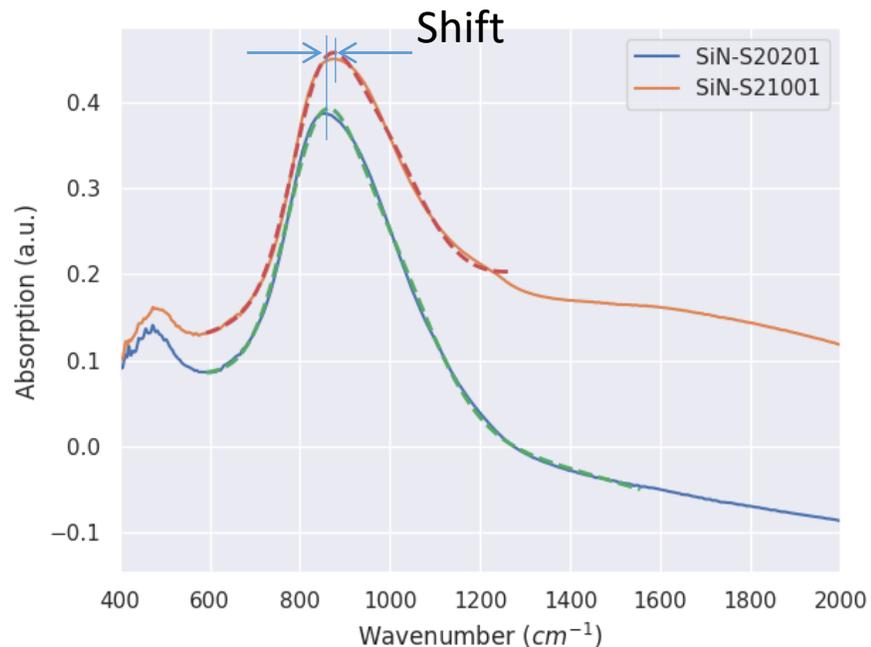
## Compositional analysis across the coating with SIMS (Padova)



## H content and vertical gradient measured with ERDA (SAFIR/Navier)



## Presence of Oxygen evaluated by FTIR (Padova)

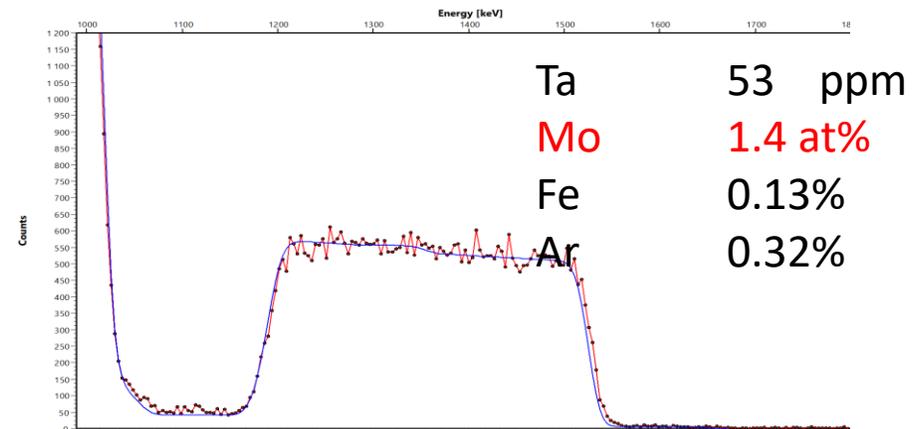
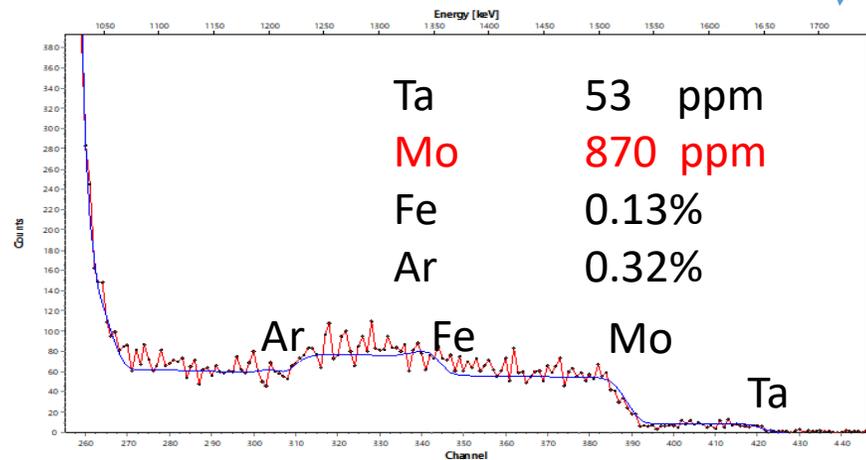
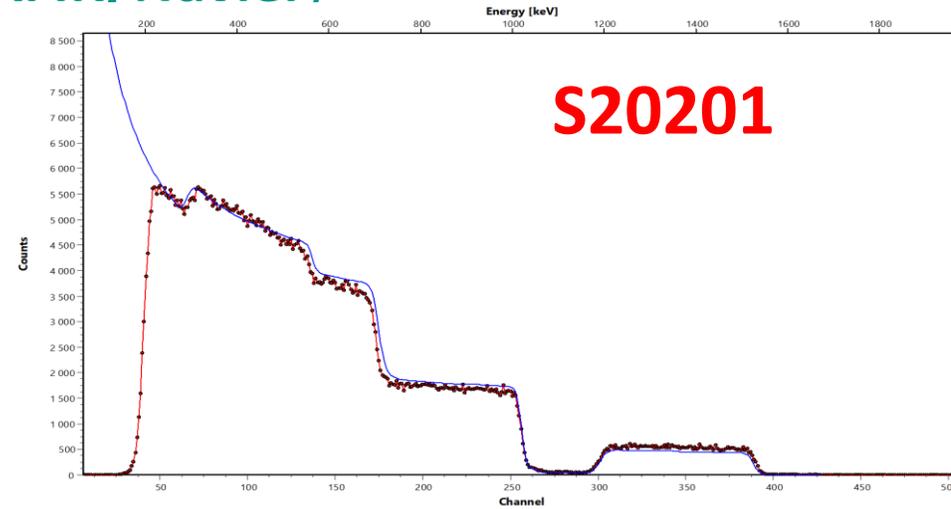
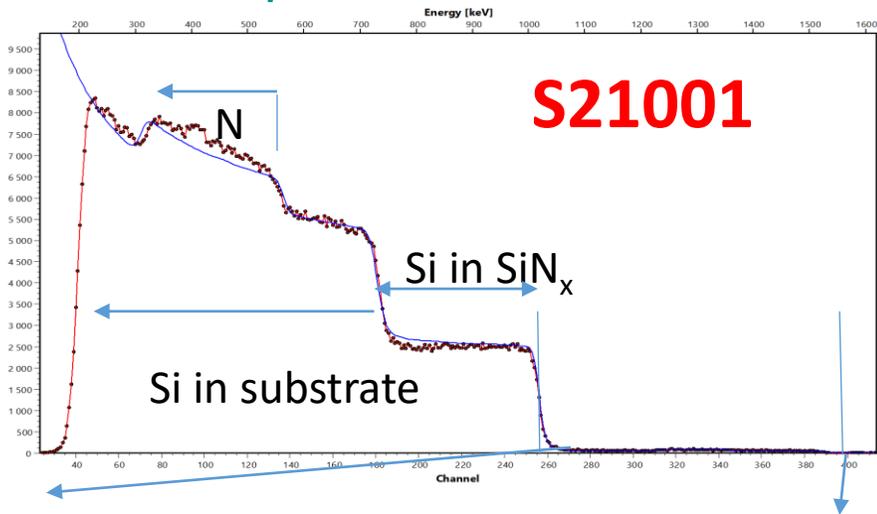


- Dominating band between 800 and 1200 cm<sup>-1</sup> is attributed to the group of Si-N and Si-O bonds.
- The main peak position shifts to larger wavenumbers by increasing the O content as the predominant bond type passes from the Si-N stretching to the Si-O stretching.
- Sample S21001 is richer in oxygen.

# Example of analysis (sample prod. date: dec2020-jan2021)

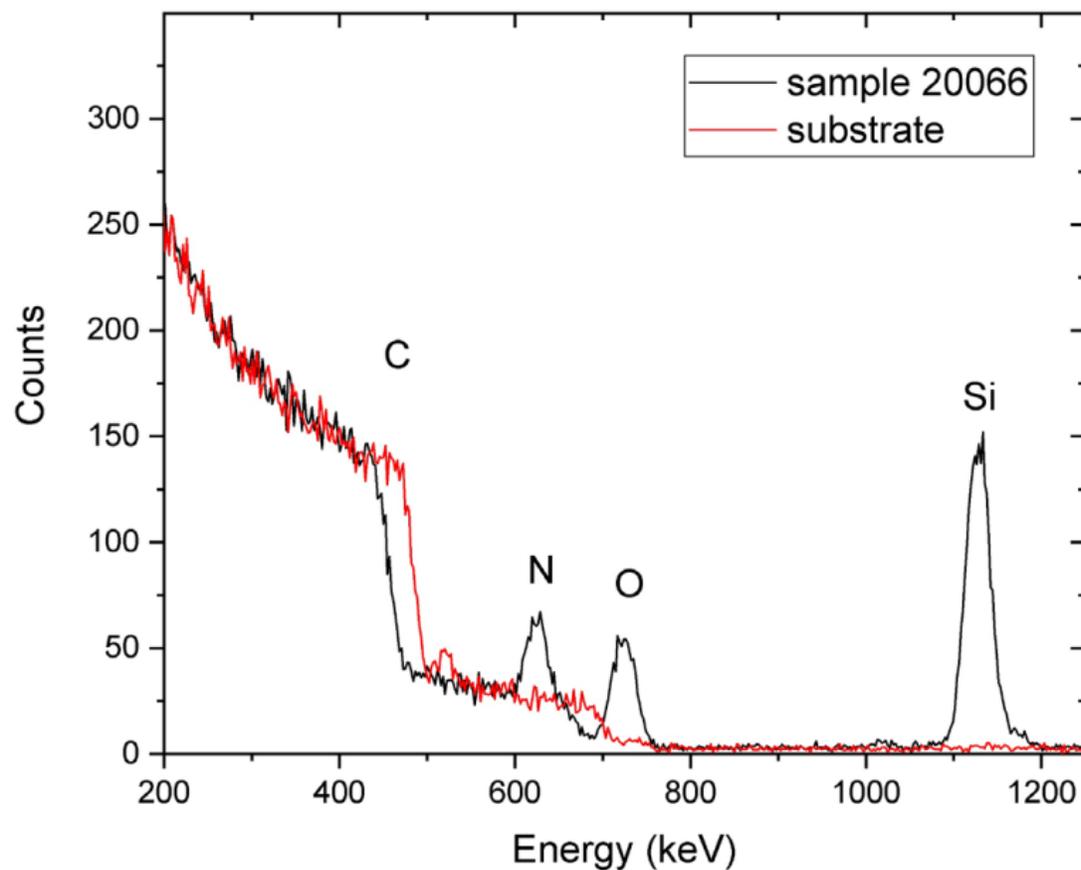


## SiN composition measured with RBS (SAFIR/Navier)



# Example of analysis (sample prod. date: spring 2020)

## SiN composition measured with RBS (Padova, previous batch)



After background subtraction:

Si =  $1.40 \times 10^{17}$  atoms/cm<sup>2</sup>

O =  $1.44 \times 10^{17}$  atoms/cm<sup>2</sup>

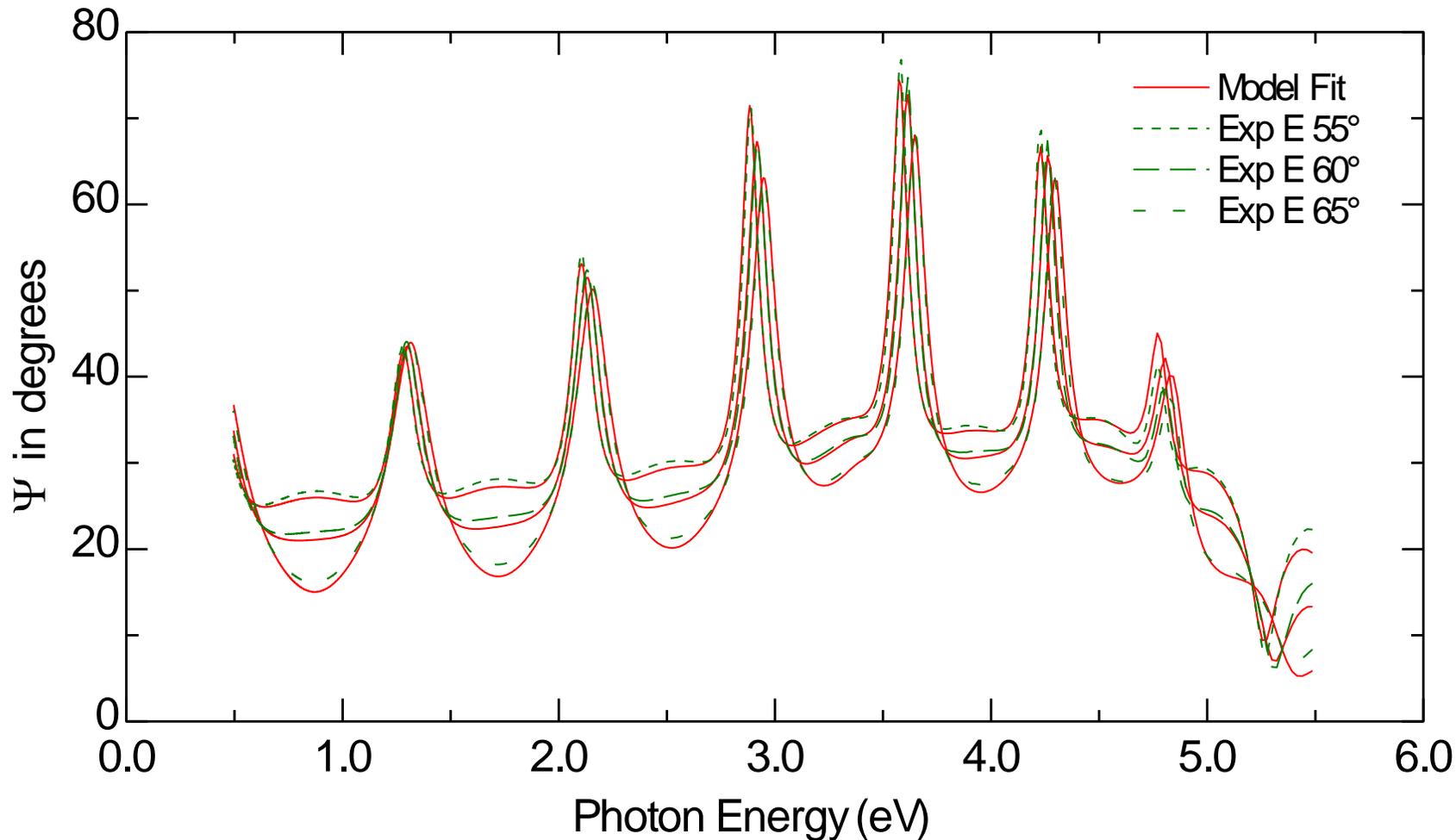
N =  $1.20 \times 10^{17}$  atoms/cm<sup>2</sup>

From these data one can obtain the corresponding atomic ratios:

N/Si=0.86

O/Si=1.03

## Presence of vertical gradient evaluated by ellipsometry (Genova)



### Model without grading

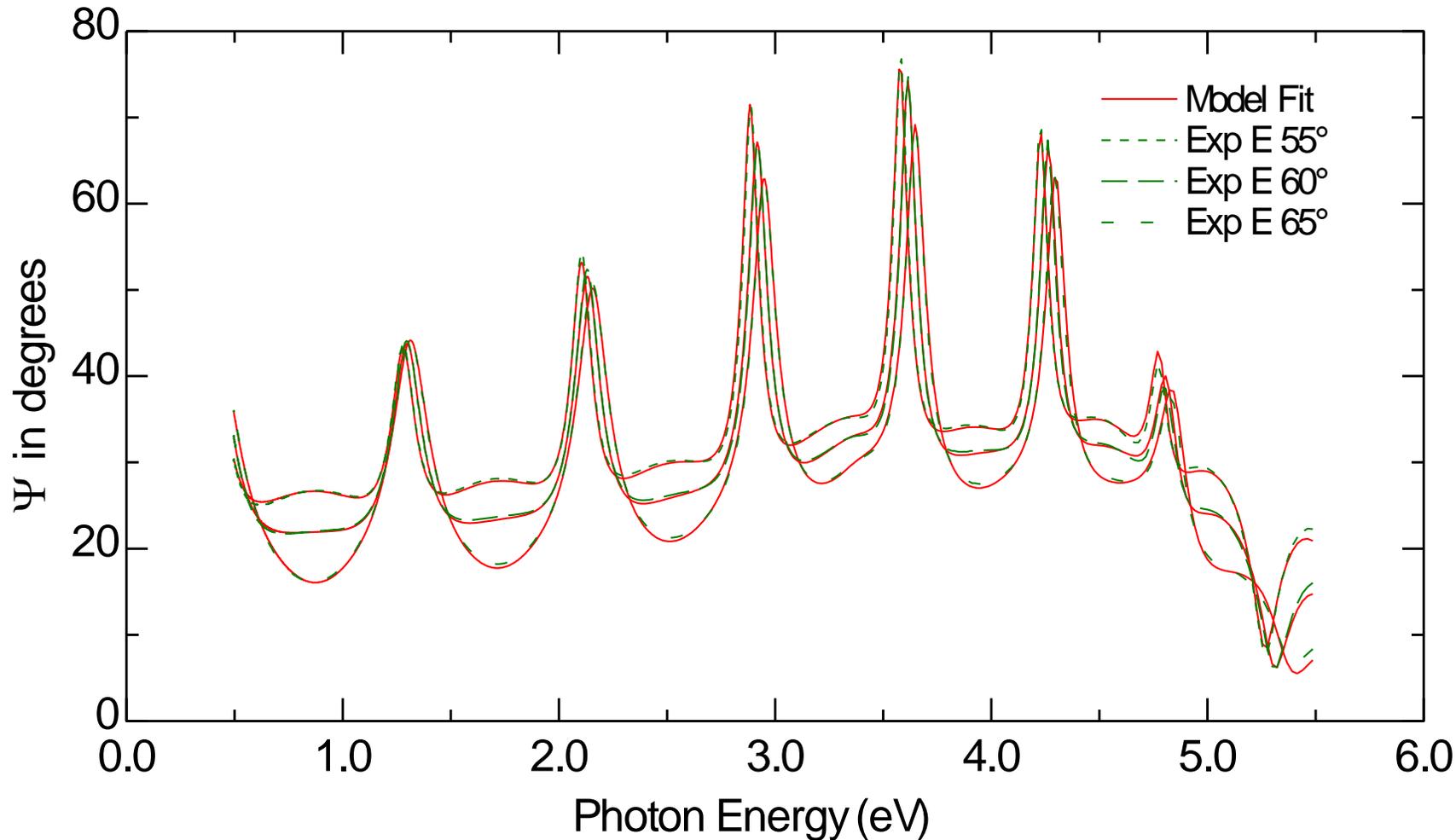
Results from SE analysis:

n@ 1064 nm: 1.90  
Thickness: 417 nm

Results from spectrophotometry:

n@1064 nm: 1.94  
Thickness: 415 nm

## Presence of vertical gradient evaluated by ellipsometry (Genova)



Results from SE analysis:

**5.7% grading**

Bottom to surface,  
 $n@1064\text{nm}$ :  
1.85-1.96

- An **intensive, cooperative effort** is ongoing to provide a comprehensive characterization of the **optical, chemical, morphological/structural properties** of the SiN films produced by LMA
- 4 SiN batches produced and characterized so far; the “performances” of the films have been continuously improved thanks to optimizations in the fabrication process and feedback provided by characterization. Examples of negative factors that have been significantly reduced:
  - water content
  - vertical inhomogeneity
- New samples will be ready soon; the collaboration is ready to characterize them
- Best results so far on SiNx films and perspectives: **see next talk by Massimo Granata**